

L Number	Hits	Search Text	DB	Time stamp
1	1493	(rta or rtp or rapid near2 thermal or thermal near2 processing or anneal or annealer or annealing) and (quartz near tube)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 09:52
2	334	(rta or rtp or rapid near2 thermal or thermal near2 processing or anneal or annealer or annealing) and (quartz near tube) and (wafer or tray or carrier or holder or chuck or support) near3 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 10:51
3	11559	(rta or rtp or rapid near2 thermal or thermal near2 processing or anneal or annealer or annealing) and (wafer or substrate) near2 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:44
4	127	(rta or rtp or rapid near2 thermal or thermal near2 processing or rapid near2 anneal\$3) and (wafer or substrate) near2 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:01
5	105	(rta or rtp or rapid near2 thermal or thermal near2 processing or anneal or annealer or annealing) and (quartz or furnace or housing) near tube same (wafer or substrate) near2 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:45
6	44	(rta or rtp or rapid near2 thermal or thermal near2 processing) and (quartz or furnace or housing) near tube same (wafer or substrate) near2 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:53
7	0	(rta or rtp or rapid near2 thermal or thermal near2 processing) and (quartz or furnace or housing) near tube same (wafer or substrate) near2 (alignment or aligning or aligned or align or position or positioning or positioner or positioned or locating or location or groove or notch or guide)	USOCR	2004/04/22 11:53
8	836	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:54
9	11	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locator or located or placement or placing or placed) near4 (notch or groove or depression or guide or rail)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:58

10	209	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locator or located or placement or placing or placed or notch or groove or guide) near4 (wafer or substrate or sample or holder or tray or carrier or chuck or support)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:59
11	172	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locator or located or placement or placing or placed or notch or groove or guide) near2 (wafer or substrate or sample or holder or tray or carrier or chuck or support)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:59
12	129	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locator or located or placement or placing or placed or notch or groove or guide) near2 (wafer or substrate or sample or holder or tray or carrier or chuck or support)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:51
13	2	("5445676" "5710407").PN.	USPAT	2004/04/22 12:15
14	3	6051512.URPN.	USPAT	2004/04/22 12:16
15	174	438/663.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:53
16	764	219/390.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:33
17	136	219/390.ccls. and (rta or rtp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:33
18	14	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locator or located or placement or placing or placed or notch or groove or guide) near2 (susceptor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:52
19	659	438/795.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:52
20	114	438/795.ccls. and (rta or rtp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:52
21	25	438/663.ccls. and (quartz or tube)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:53